PLASMA PROCESSING APPARATUS

Abstract

The present disclosure provides a plasma processing apparatus comprising: a plasma processing chamber; a substrate support; an electrode or an antenna; a radio frequency power supply; a power receiving coil electrically connected to said at least one power-consuming member; a power transmitting coil electromagnetically inductively coupled with the power receiving coil; a power transmitting part electrically connected to the power transmitting coil to supply a power to the power transmitting coil; and a controller. The power transmitting part includes a voltage detector and a current detector, and the controller is configured to determine a required power level corresponding to a parameter value including an input impedance obtained from the input voltage and the input current or a load resistance value of said at least one power-consuming member, and to control the power transmitting part to output an output power having the required power level.

Fig. 27